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Abstract**Aqueous Dispersions, Process for their Production, and
their Use**

- 5 The invention provides an aqueous dispersion containing a
cerium oxide-doped, pyrogenically produced silicon dioxide,
wherein the cerium oxide is introduced through an aerosol
of a cerium salt solution or suspension and the average
particle size in the dispersion is less than 100 nm. The
10 dispersion is produced by dispersing the cerium oxide-
doped, pyrogenically produced silicon dioxide in aqueous
solution by means of a high energy input. The aqueous
dispersion can be used for chemical-mechanical polishing.



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